

*ABSTRACT AMENDMENTS*

Replace the Abstract with:

A method for manufacturing a thin-film semiconductor includes ~~the step of~~ polycrystallization to focus visible light pulse laser ~~(22)~~ into a line shape on a surface of an object to be irradiated, and repeat irradiation with displacing the visible light pulse laser ~~(22)~~ such that a line-shaped irradiated region ~~(35)~~ is overlapped with a region ~~(35)~~ irradiated at a next timing in a width direction of the line-shaped irradiated region, to form a polycrystalline silicon film on the surface of the object. The step of polycrystallization applies ultraviolet light pulse laser ~~(23)~~ onto a second irradiated region ~~(36)~~ partially overlapping the first irradiated region ~~(35)~~ while or before the visible light pulse laser ~~(22)~~ is applied to the first irradiated region ~~(35)~~.